

AMENDMENTS TO THE CLAIMS:

1. (Currently amended) A processing apparatus for processing a workpiece, comprising:
a cover for covering a portion of a surface, to be processed, of said the workpiece;
a process chamber to be formed by said cover and said the surface, to be processed, of said the workpiece; and
a sealing portion provided at a lower end of said cover for sealing said process chamber when formed, said sealing portion to be provided between said cover and said the surface of said the workpiece for sealing said process chamber so as to face the surface of the workpiece.
2. (Currently amended) ~~A~~ The processing apparatus according to claim 1, wherein said sealing portion comprises at least one of a contact seal and a non-contact seal.
3. (Currently amended) A processing apparatus ~~according to claim 2, for processing a workpiece, comprising:~~
a cover for covering a portion of a surface, to be processed, of the workpiece;
a process chamber to be formed by said cover and the surface, to be processed, of the workpiece; and
a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed, said sealing portion comprising at least one of a contact seal and a non-contact seal,
wherein said contact seal comprises at least one of an O-ring and an oil seal.
4. (Currently amended) A processing apparatus ~~according to claim 2, for processing a workpiece, comprising:~~
a cover for covering a portion of a surface, to be processed, of the workpiece;
a process chamber to be formed by said cover and the surface, to be processed, of the workpiece; and

a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed, said sealing portion comprising at least one of a contact seal and a non-contact seal,

wherein said non-contact seal comprises at least one of a magnetic fluid seal and a differential pumping seal.

5. (Currently amended) A processing apparatus according to claim 1, further comprising for processing a workpiece, comprising:

a cover for covering a portion of a surface, to be processed, of the workpiece;

a process chamber to be formed by said cover and the surface, to be processed, of the workpiece;

a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed; and

a chemical vapor deposition device in said process chamber, when formed, for depositing a thin film on said the surface of said the workpiece.

6. (Currently amended) A processing apparatus according to claim 1, further comprising for processing a workpiece, comprising:

a cover for covering a portion of a surface, to be processed, of the workpiece;

a process chamber to be formed by said cover and the surface, to be processed, of the workpiece;

a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed; and

a chemical liquid cleaning device in said process chamber, when formed, for cleaning said the surface of said the workpiece with a chemical liquid.

7. (Currently amended) A processing apparatus according to claim 1, further comprising for processing a workpiece, comprising:

a cover for covering a portion of a surface, to be processed, of the workpiece;

a process chamber to be formed by said cover and the surface, to be processed, of the workpiece; and

a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed; and

a sensor for detecting conditions of said the surface of said the workpiece.

8. (Currently amended) ~~A~~ The processing apparatus according to claim 7, further comprising an adjustment device for adjusting processing conditions in said process chamber, when formed, based on a signal from said sensor.

9. (Currently amended) A processing apparatus according to claim 1 for processing a workpiece, comprising:

a cover for covering a portion of a surface, to be processed, of the workpiece;

a process chamber to be formed by said cover and the surface, to be processed, of the workpiece; and

a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed,

wherein said the surface of said workpiece is to be processed under a pressure lower than atmospheric pressure.

10. (Currently amended) A processing apparatus according to claim 1 for processing a workpiece, comprising:

a cover for covering a portion of a surface, to be processed, of the workpiece;

a process chamber to be formed by said cover and the surface, to be processed, of the workpiece; and

a sealing portion to be provided between said cover and the surface of the workpiece for sealing said process chamber when formed,

wherein said the surface of said the workpiece is to be processed under a wet condition.

Claims 11-17 (cancelled)